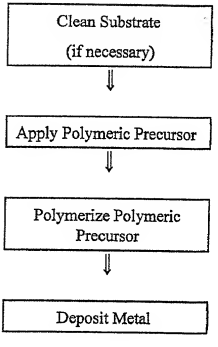
Clean Substrate
(if necessary)
Apply Polymeric Precursor
Polymerize Polymeric Precursor
Deposit Metal

FIG. 1

TOTTHO' 9L08228O

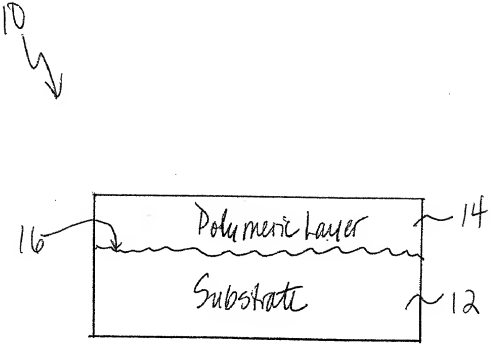

FIG.2

PATENT-SD0336

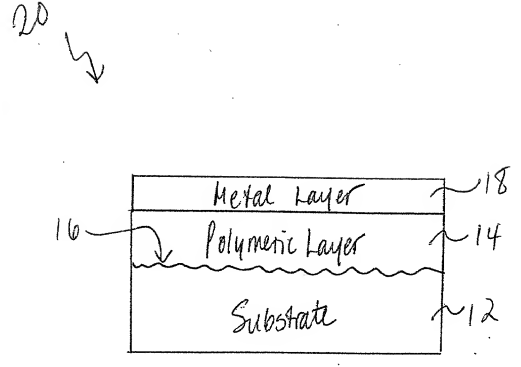

FIG. 3

TOKYO 92083860

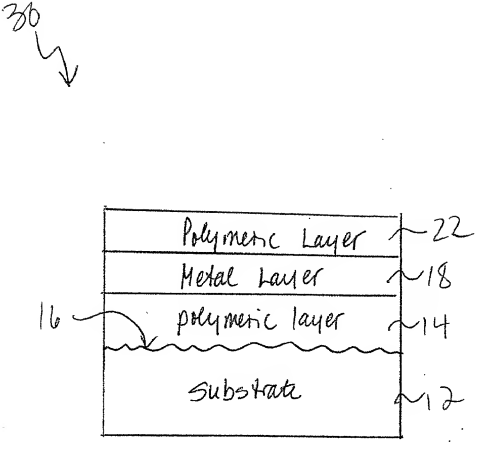

FIG. 4